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## [May 06, 2010] The MEDEA+ FOREMOST Advanced Technology R&D Project: Short-listed for 2010 EUREKA Innovation Award

A. May 6. 2010 /PRNewswire via COMTEX/ -- STMicroelectronic MEDEA+ FOREMOST Integration of 45nm CMOS technology<sup>4</sup> Advanced R&D project, today announced that FOREMOST has been short-listed as one of three inalists for the 2010 EUREKA Innovation Award

The EUREKA German Chairmanship invited one member from each of the three short-listed projects at the EUREKA stand at the Hannover Messe (April 19-20.) in Germany. The three finalists will also be invited to the award ceremony itself, which will take place in Berlin on Thursday 24 June 2010. The overall winner of the award will be announced at this cer attended by numerous European dignitaries, including ministers and ambassadors

The MEDEA+2T103 FOREMOST project, which was suc sfully comp was launched in January 2006 with the goal of maintaining Europe's strength in CMOS integrated circuit technology and manufacturing, through the development, integrated integrated circuit technology and manufacturing, through the development, integration, and demonstration of advanced process modules and transistor architectures for full 45nm node technology in industrial 300 mm wafer fabrication plants. It was notably supported by the national authorities of France, Germany and the Netherlands, among others, working tog within the frame of the EUREKA MEDEA+ program.

ed both CMOS logic and DRAM/FLASH memory process technologies, v e pro ct targe the aim of promoting synergy between the competences of leading European semiconductor manufacturers (including STMicroelectronics, NXP, Freescale, Qimonda), as well as essentia erial and equipment suppliers (Air Liquide, Aixtron, ASM ) and world-class institutes and laboratories. (See note (1) for the complete list of FOREMOST consortium members)

The project achieved all of its main goals and it paved the way for new challenging syst ip developments. In addition, project partners published more than 80 papers, filed 30 patent applications, and gave presentations at more than 40 conferences. The impact of new pat successful R&D projects such as FOREMOST can be measured through subsequent ts in major fields of application that boost the position of Europe's chipma such as STMicroelectronics and their equipment and materials suppliers in the world market

ns field, ST-Eric le, in the m on, a glo platforms and semiconductors, demonstrated a dual-core smartphone platform, with each core running at a clock speed of 1.2 GHz, at the Mobile World Congress in February 2010. The performance breakthrough, which set a new benchmark for an integrated smartphone platf on a multicore system, will enable handsets to run several graphically-rich applications simultaneously, integrating HD or 3D video and social networking with online map-navig and augmented reality. It will also dramatically enhance the responsiveness and experience of the smartphone user interface. The USSO was designed on STMicroelectronics' leading-ed low-power 45nm process, which is a key enabler to achieve the performance demonstrated. the Congress.

Similarly, in the Home Entertainment and Displays field, STMicroelectronics demonstrat potential of the STi7108 at the January 2010 Consumer Electronics Show (CES) in Las Vegas. The STi7108 is the first in ST's third generation of high-definition chips uses unprecedented CPU performance to provide the end user with an exciting 3D HDTV user experience. It also delivers market-leading energy efficiency, using its low-p architecture and ST's low-power manufacturing process. er, configurable

"This EUREKA Innovation Award recognizes the collective ve effort of Europ from leading chip manufacturers, equipment and material suppliers including SMEs (Small and Medium Enterprise's) to industry-oriented research institutions and universities, partnering to develop advanced knowledge that will enable the European chip industry to maintain its stror nced know in its strong presence in the worldwide microelectronics landscape." said Dr. Dominique Thomas. roelectronics Technology R&D, Director, Partnership Programs, 'Consistency bel ssive generation of projects supported by the EUREKA initiatives JESSI, MEDEA, STMicroe MEDEA+ and now CATRENE, as well as European Commission supported Program enables the development and utilization of successive technology node generations optimized. FOREMOST used outputs from the EU Sixth Framework Program (FP6) NANOCMOS project, which carried out initial screening and demonstration of app materials, device and interconnect architectures for 45nm CMOS logic. In parallel, PULLNANO, another FP6 project, built upon the successful NANOCMOS project and focused on the early development of 32mm CMOS technology nodes, opening the way to European access to this technology. PULLNANO, successfully concluded at the end of 2008, has been selected as a so-called "STAR" project for the ICT 2010 event to be held September 27-29 2010 in Bru

More information about FOREMOST <a href="http://www.cattene.org/web/medeaplus">http://www.cattene.org/web/medeaplus</a> <a href="http://web/medeaplus">http://www.cattene.org/web/medeaplus</a> </a> (Instruction of France), ASM International (The Netherlands), EA-LETI (France), CNR-INFM-MDM (Italy), Fraunofor CNT (Germany), Freescale (France), IBS (France), IMEC (Belgium), INPG-IMEP (France), Jordan Valley (Israel), LAHC Universite de Savoie (France), LMGP (France), LTM-UJF (France), NCSR Demokritos (Greece), NXP Semiconductors (France Names, Trin Gelgium), Climonda Dresden (Germany), SAFC Hitech (United Kingdon), NAP research (Belgium), Climonda Dresden (Germany), SAFC Hitech (United Kingdon), Vistec Electron Beam (Germany), (2) List of the 38 PULLNANO consortium members: STMicroelectronics SA (France, Project Coordinator), STMicroelectronics (Crolles2) SAS (France), NXP Semiconductors Crolles R&D (France), Freescale Semiconducteurs Centre de erche Crolles SAS (France), NXP Semiconductors Belgium NV (Belgium), Ph Electronics Nederland B.V. (Nederland), Infineon Technologies AG (Germany), Qimonda Dersden (Germany), STMicroelectronics S.r.I. (Italy) later on Numonyx (Italy), Interuniversitair Micro-Elektronica Centrum vzw (Belgium), Commissariat a l'Energie Atomique (LETI) (France), Fraunhofer-Gesellschaft zur Foerderung der angewandten Forschung e.V. (Germany), Centr National de la Recherche Scientifique (France), Technische Universitaet Chernitz ( University of Newcastle upon Tyne (United Kingdom), Universite de Savoie (France), Technische Universitaet Wien - Institut fuer Mikroelektronik (Austria), Universite Catho Louvain (Belgium), Consorzio Nazionale Interuniversitario per la Nanoelettronica (IU.NET) (Italy), Swiss Federal Institute of Technology (ETH) (Switzerland), University of Glasgow (United Kingdom), Warsaw University of Technology (Poland), Chalmers University Technology (Sweden), AMO GmbH (Gesellschaft fur angewandte Mikro- und Opto rsity of (Germany), Forschungszentrum Juelich GmbH (Germany), The University of Liverpool (United Kingdom), National Technical University of Athens (Greece), University College Cork), National University of Ireland (Ireland), University of Warwick (United Kingdom), Europ Synchrotron Radiation Facility (France), The University of Surrey (United Kingdom), Educy Services (France), Integrated Systems Development S.A. (Greece), Magweil NV (Belgi Acies (France), Cameca (France), Nova (Israel), and Imagine optics (France). m), Ion Be

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